

LED TYPE I: WITH InAIGaN LIGHT-EMITTING LAYER (EMISSION

WAVELENGTH $\lambda = 308$ nm)

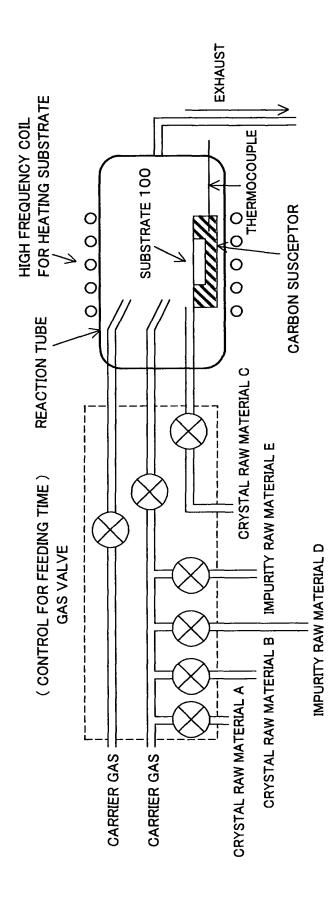
 $(In_xAl_yGa_{1-x-y}N: x=0.02, y=0.44)$

LED TYPE II: WITH InAIGaN LIGHT-EMITTING LAYER (EMISSION

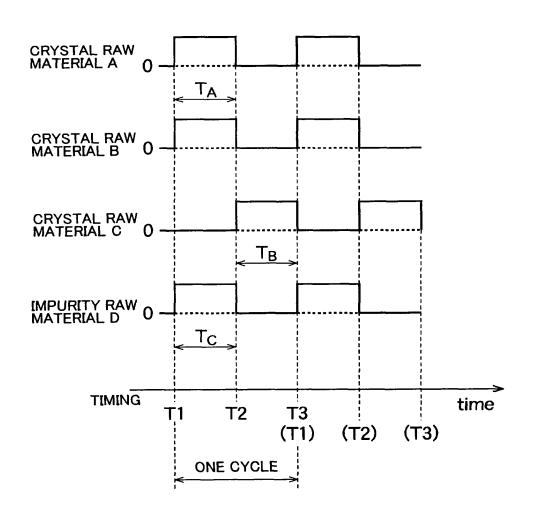
WAVELENGTH $\lambda = 314$ nm)

 $(In_xAl_yGa_{1-x-y}N: x=0.02, y=0.40)$

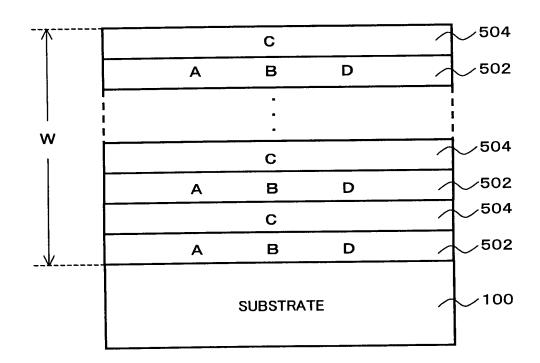
LED TYPE III: WITHOUT InAIGaN LIGHT-EMITTING LAYER



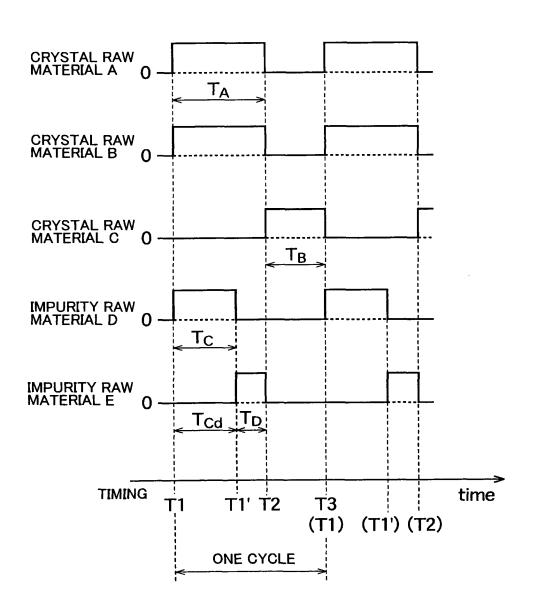
SEQUENCES IN PULSES FOR FEEDING RAW MATERIALS



CRYSTAL STRUCTURE FORMED IN ACCORDANCE WITH TIMINGS SHOWN IN FIG. 3

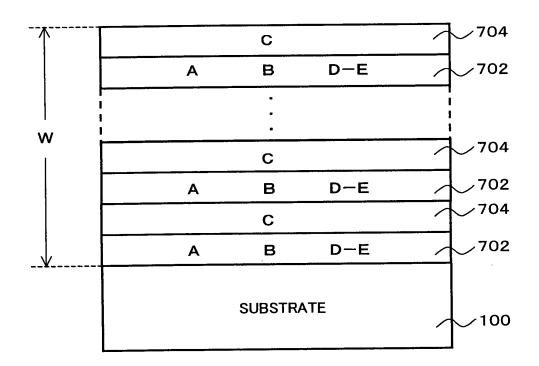


SEQUENCES IN PULSES FOR FEEDING RAW MATERIALS

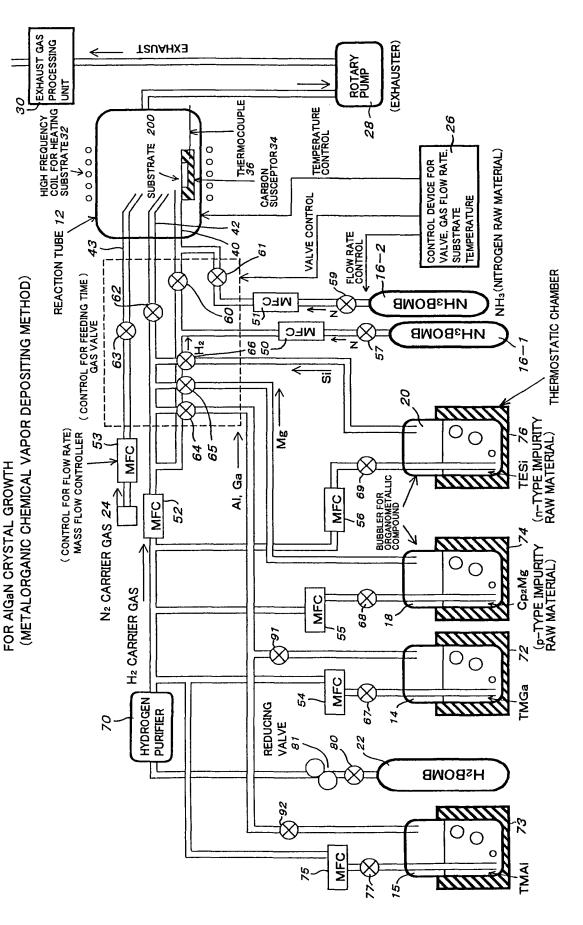


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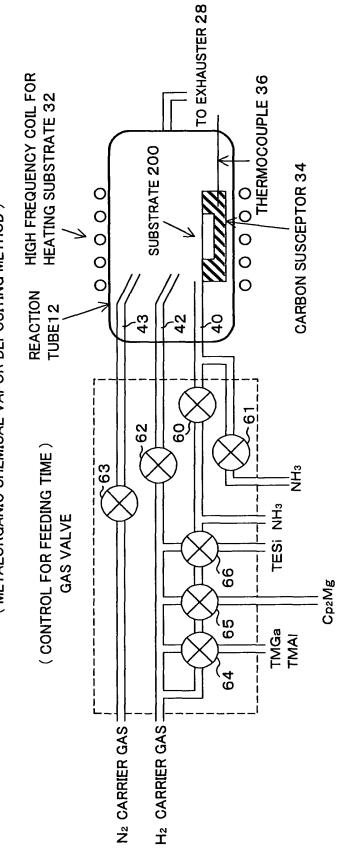
CRYSTAL STRUCTURE FORMED IN ACCORDANCE WITH TIMINGS SHOWN IN FIG. 5



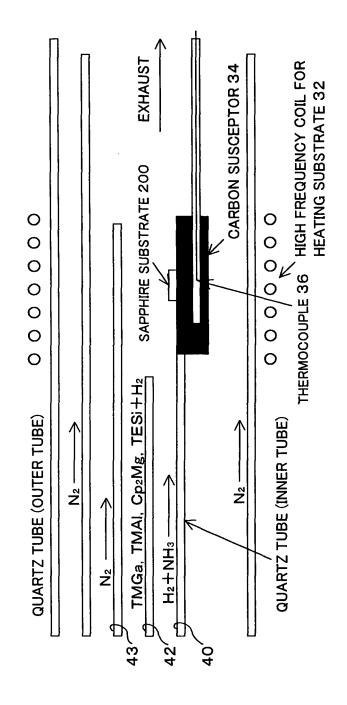
METALORGANIC CHEMICAL VAPOR DEPOSITING APPARATUS



METALORGANIC CHEMICAL VAPOR DEPOSITING APPARATUS FOR AIGAN CRYSTAL GROWTH 10 (METALORGANIC CHEMICAL VAPOR DEPOSITING METHOD)



SCHEMATIC DIAGRAM FOR MOCVD REACTION TUBE



PRESSURE IN REACTION TUBE: 76Torr

SEQUENCES OF PULSES FOR FEEDING RAW MATERIALS IN CASE OF FORMING AIGaN

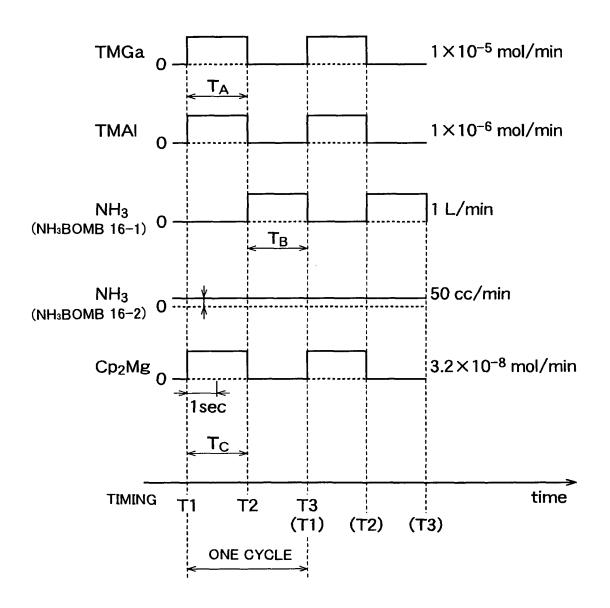
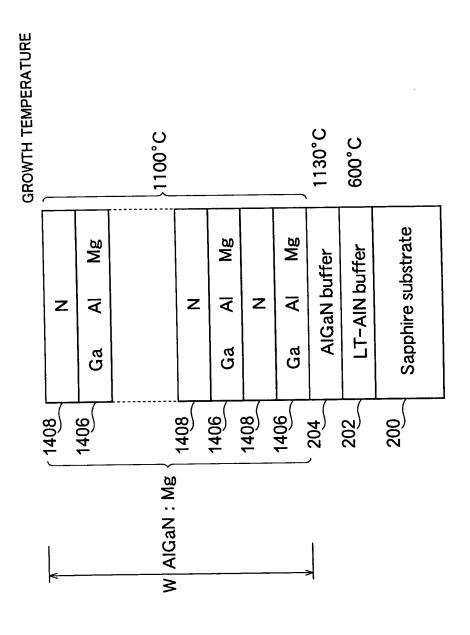


FIG. 11



SEQUENCES OF PULSES FOR FEEDING RAW MATERIALS IN CASE OF FORMING AIGaN

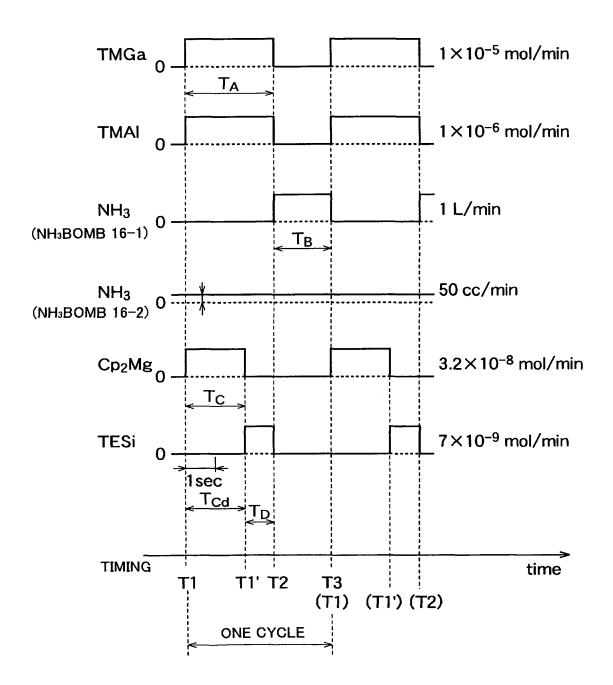
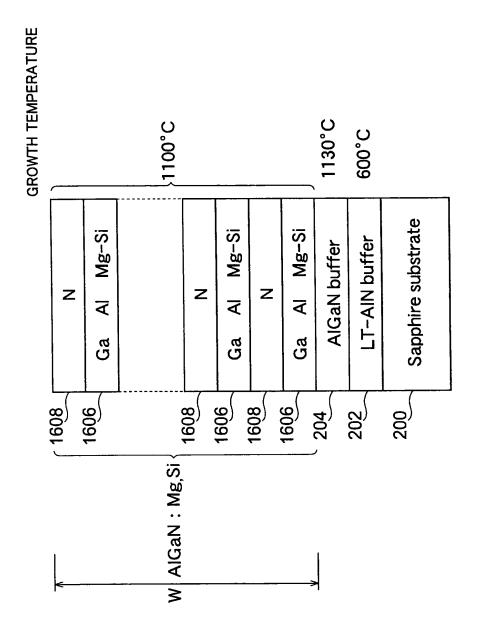
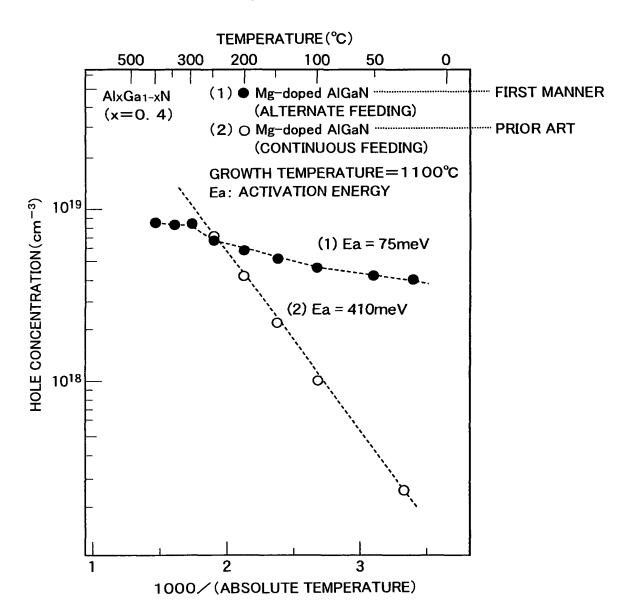


FIG. 13

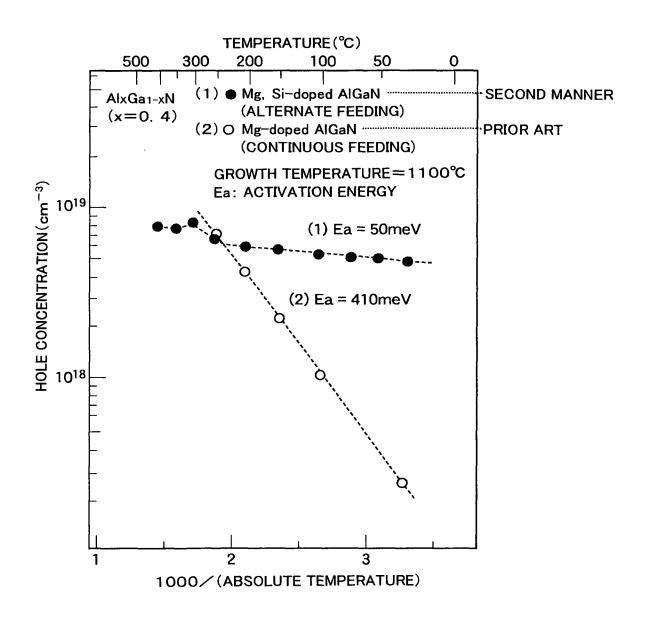


4, 1,1 1,1

TEMPERATURE DEPENDENCE OF HOLE CONCENTRATION IN AIGAN DOPED WITH Mg

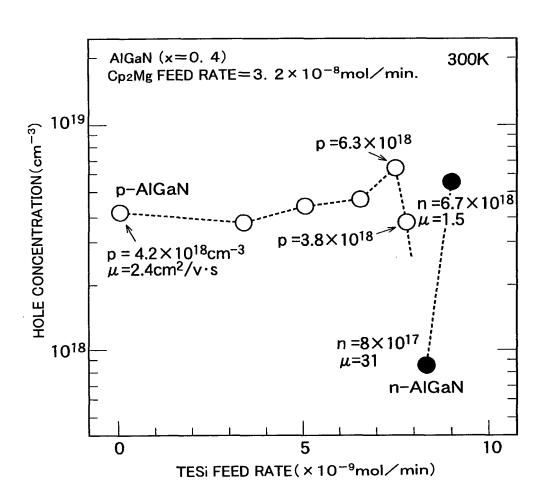


TEMPERATURE DEPENDENCE OF HOLE CONCENTRATION IN AIGAN DOPED WITH Mg AND Si

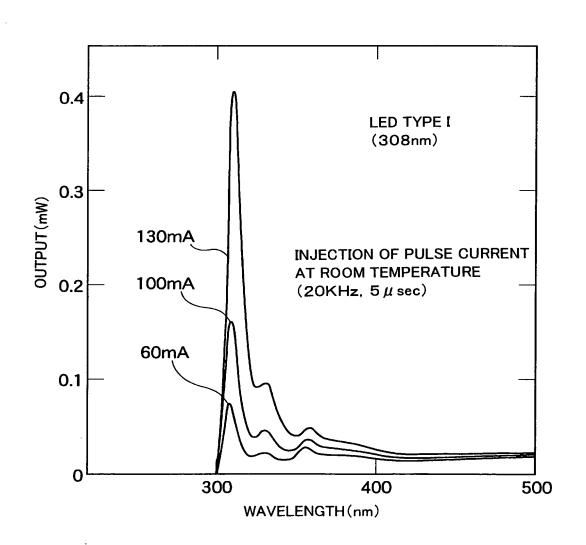


1, 140 M

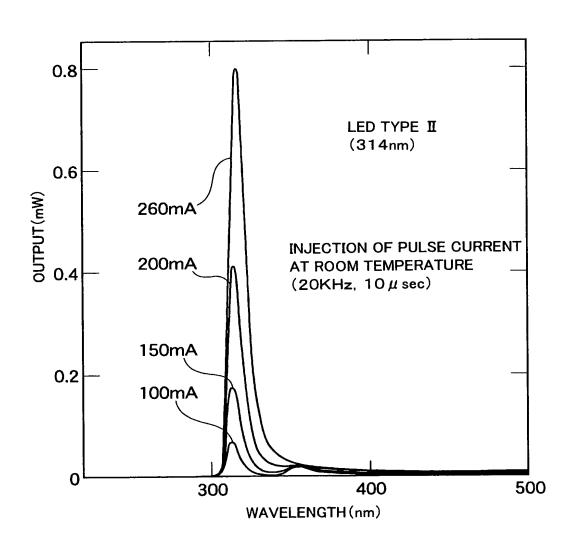
DEPENDENCE OF SI FEED RATE IN HOLE CONCENTRATION OF AIGAN DOPED WITH Mg-Si



ULTRAVIOLET OUTPUT SPECTRA OF LED TYPE I



ULTRAVIOLET OUTPUT SPECTRA OF LED TYPE II



ULTRAVIOLET OUTPUT SPECTRA OF LED TYPE III

